

SYSTEM AND METHOD FOR MEASURING PROPERTIES OF A
SEMICONDUCTOR SUBSTRATE IN A NON-DESTRUCTIVE WAY
Clarysse et al.
Appl. No.: Unknown Atty Docket: IMEC281.001AUS

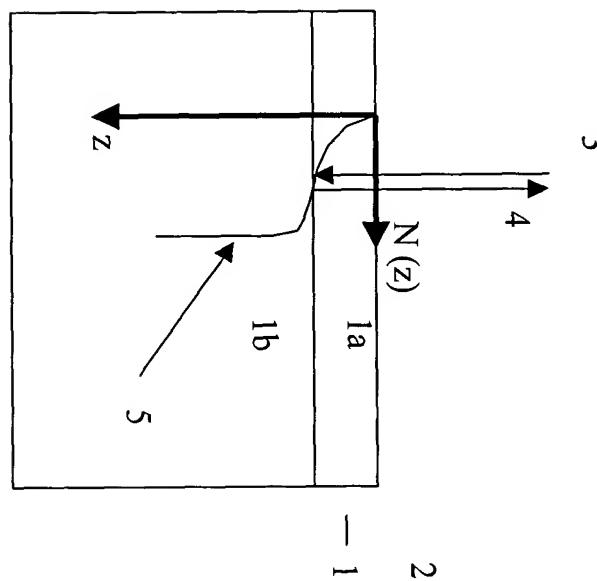
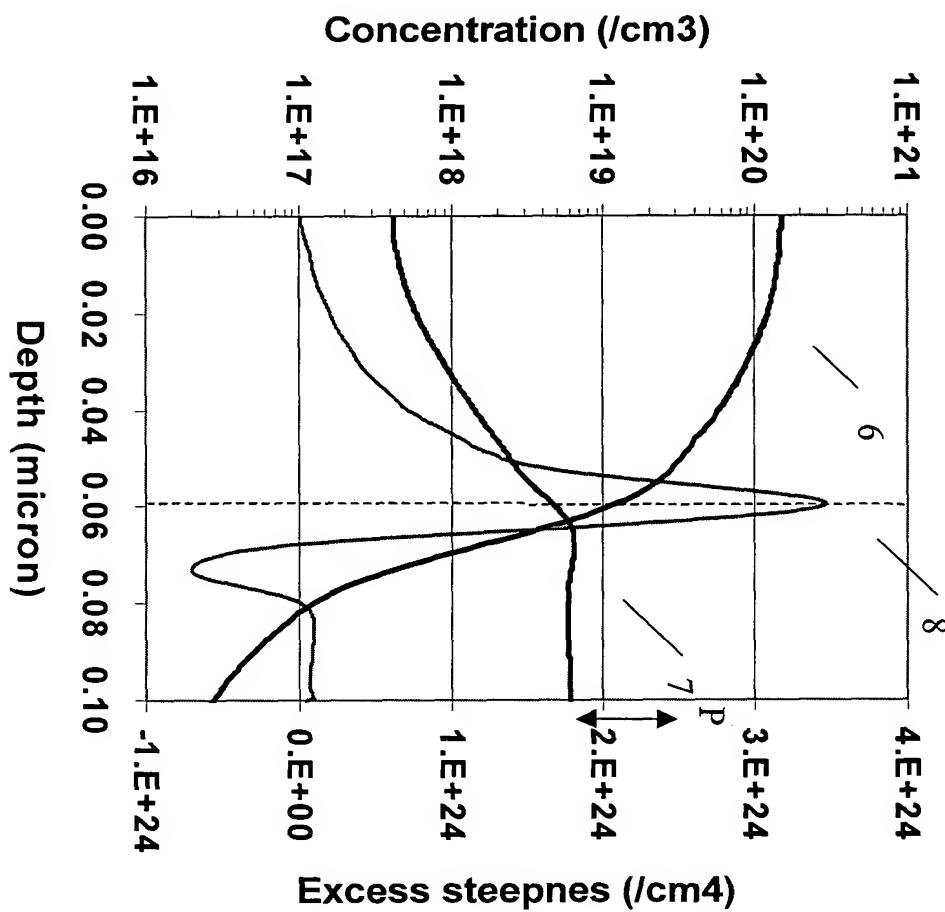


Figure 1

Figure 2



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Figure 3a

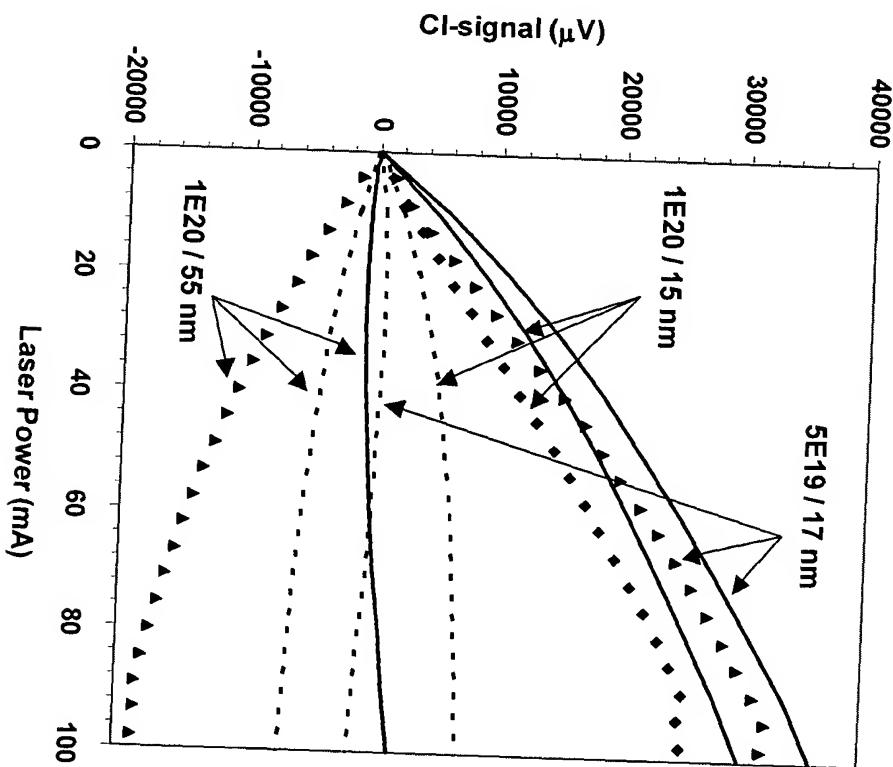
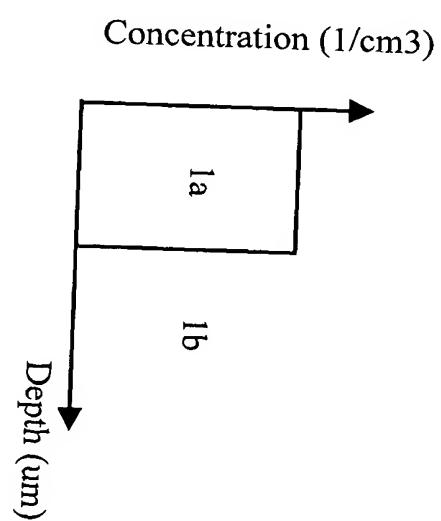


Figure 3b



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Figure 4

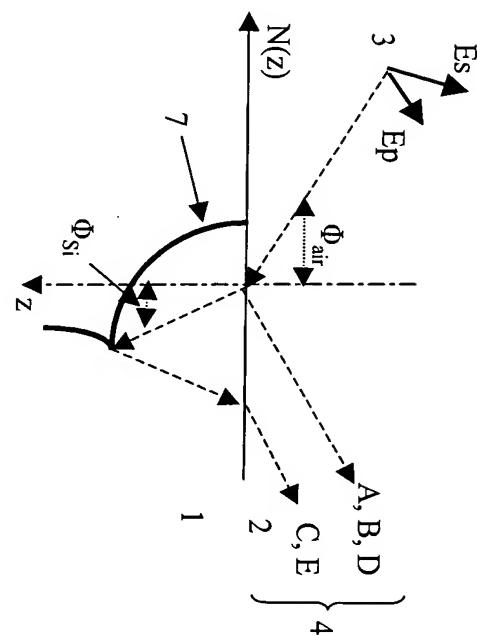


Figure 5

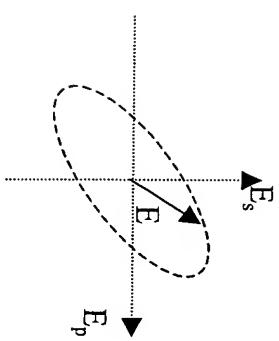


Figure 6b

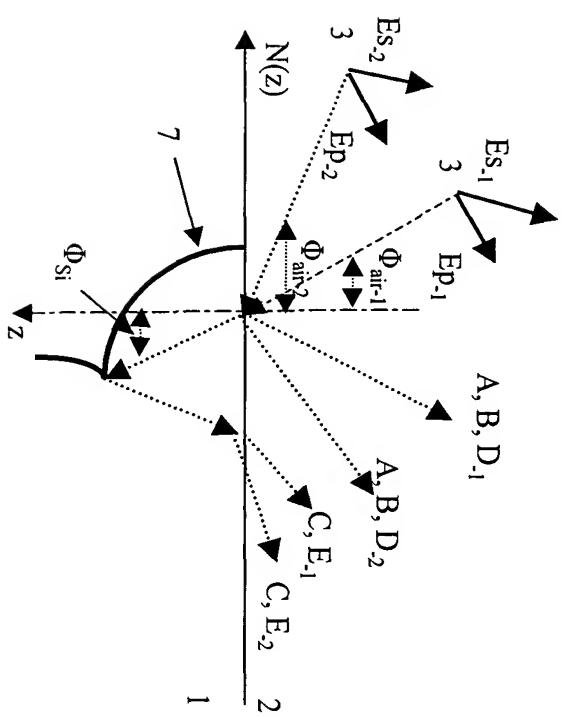
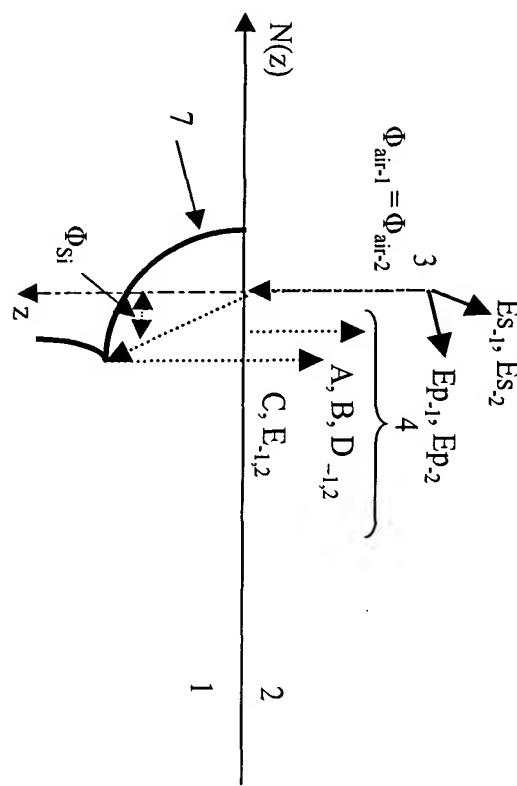


Figure 6a

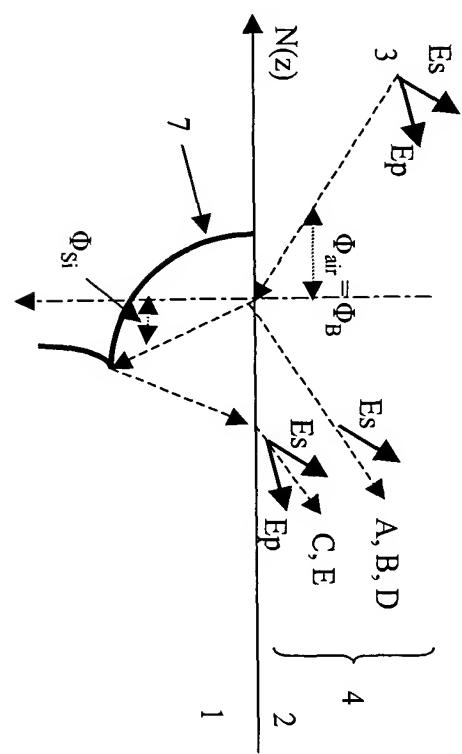


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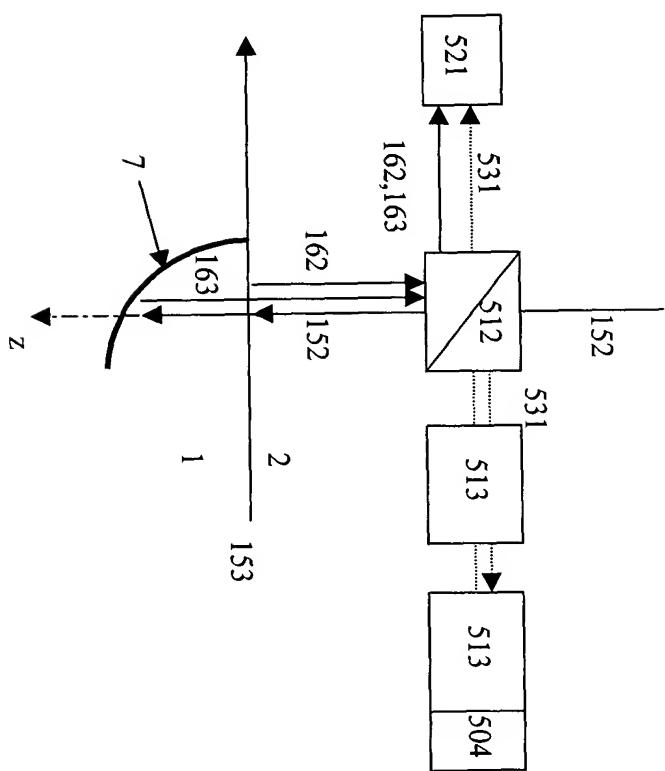
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Figure 7



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Figure 8



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Figure 9

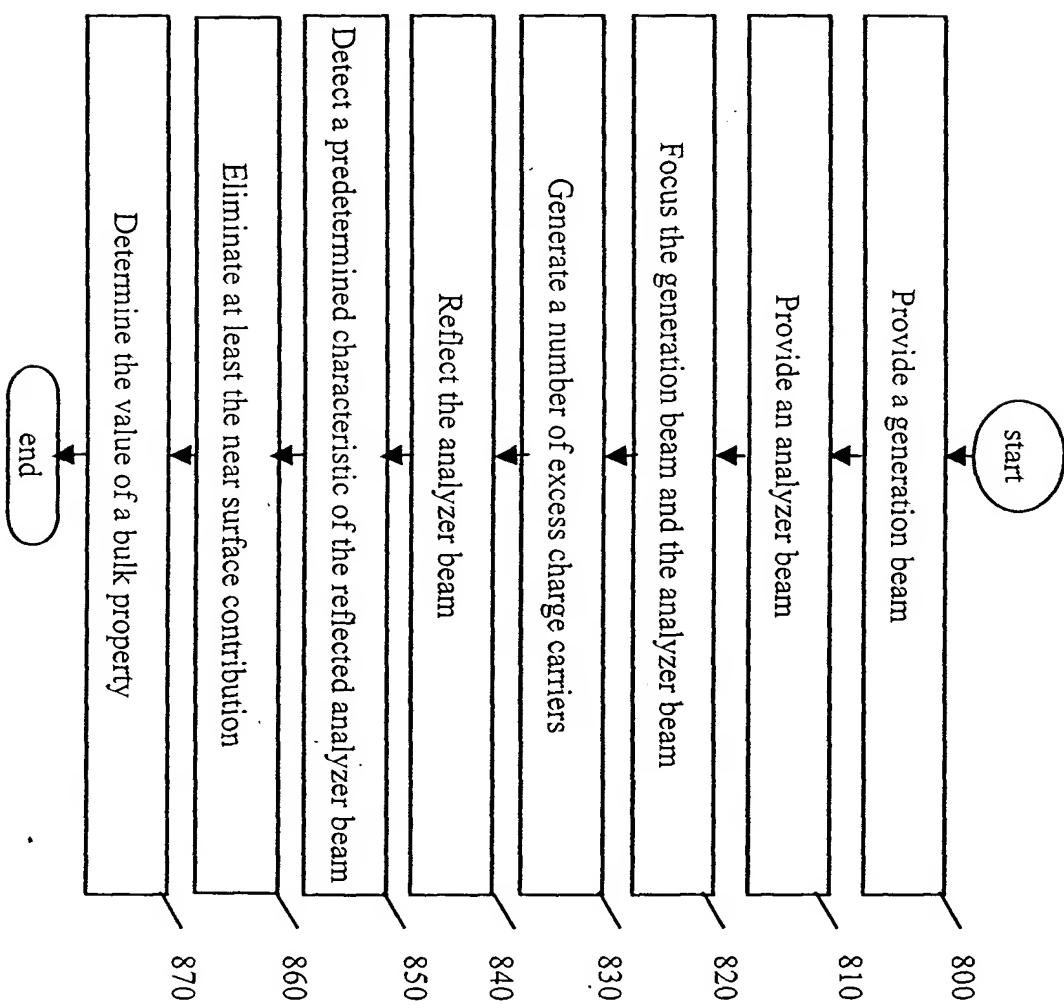


Figure 10

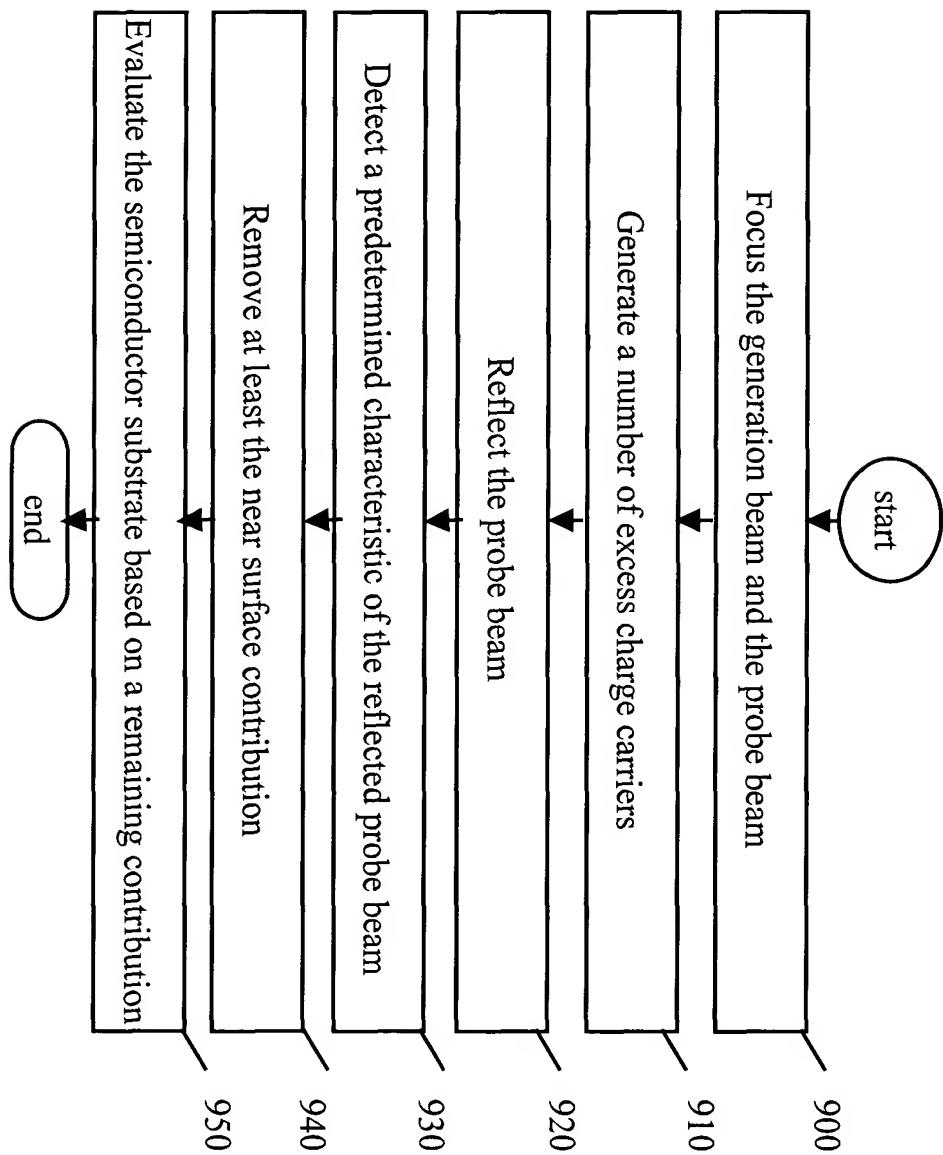


Figure 11

